

PROCESS FOR DEPOSITING TITANIUM OXIDE USING A PLASMA SOURCE

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ABSTRACT

Process for depositing, on a substrate, a coating based on titanium oxide, which is characterized in that the coating with photocatalytic properties is deposited by chemical vapor deposition, especially from a gas mixture comprising at least one organometallic precursor and/or a metal halide of said metal oxide, the deposition being enhanced by a plasma source.